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TRANSMITTAL OF INFORMATION DISCLOSURE STATEMENT Docket No. (Under 37 CFR 1.97(b) or 1.97(c)) BUR920040086US1 In Re Application Of: Rankin et al. Customer No. Group Art Unit Confirmation No. Application No. Examiner Filing Date 024241 07/23/04 Unassigned 10/710602 Title: METHOD TO SELECTIVELY CORRECT CRITICAL DIMENSION ERRORS IN THE SEMICONDUCTOR Address to: **Commissioner for Patents** P.O. Box 1450 Alexandria, VA 22313-1450 37 CFR 1.97(b) The Information Disclosure Statement submitted herewith is being filed within three months of the filing of a national application other than a continued prosecution application under 37 CFR 1.53(d); within three months of the date of entry of the national stage as set forth in 37 CFR 1.491 in an international application; before the mailing of a first Office Action on the merits, or before the mailing of a first Office Action after the filing of a request for continued examination under 37 CFR 1.114. 37 CFR 1.97(c) The Information Disclosure Statement submitted herewith is being filed after the period specified in 37 CFR 1.97(b), provided that the Information Disclosure Statement is filed before the mailing date of a Final Action under 37 CFR 1.113, a Notice of Allowance under 37 CFR 1.311, or an Action that otherwise closes prosecution in the application, and is accompanied by one of: ☐ the statement specified in 37 CFR 1.97(e); OR ☐ the fee set forth in 37 CFR 1.17(p).

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In Re Application	n: Rankin et al.	AUG 0 9 2004											
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METHOD TO SELECTIVELY CORRECT CRITICAL DIMENSION ERRORS IN THE													
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	(Only cor	mplete if Applicant ele	cts to pay the f	ee set forth in 37	CFR 1.17(p))								
 □ A check in the amount of is attached. ☑ The Director is hereby authorized to charge and credit Deposit Account No. ☑ Substituting the amount of is attached. ☑ Charge the amount of is attached. ☑ Credit any overpayment. ☑ Charge any additional fee required. ☑ Certificate of Mailing by First Class Mail 													
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William D. Sabo, Esc Reg. No.: 27,465 I P Law Department IBM Microelectronic 1000 River Street - Essex Junction, VT	Signature Signature 972E 05452	if paying by	Dated: /	Aug. J	, 2004 1	4							
Tel. No.: 802-769-94	54												



IN THE UNITED STATES PATENT AND TRADEMARK OFFICE PATENT APPLICATION

Applicant:

Rankin et al.

Serial No.: 10/710602

Filed:

07/23/2004

Atty. Docket: BUR920040086US1

Title:

METHOD TO SELECTIVELY CORRECT CRITICAL DIMENSION ERRORS

IN THE SEMICONDUCTOR INDUSTRY.

SUPPLEMENTAL INFORMATION DISCLOSURE STATEMENT UNDER 37 CFR 1.56, 1.97, 1.98

Honorable Commissioner of Patents and Trademarks Washington, D. C. 20231

Sir:

Applicants submit herewith form PTO-1449, listing patents, publications, or other information of which they are aware which they believe may be material to patentability pursuant to 37 CFR 1.56(b), and in respect of which there may be a duty to disclose under 37 CFR 1.56(a), together with legible copies of the patents, publications, or other information listed.

While the items submitted with this Information Disclosure Statement may be material to patentability pursuant to 37 CFR 1.56, in accordance with 37 CFR 1.97(h) it shall not be construed to be an admission that any patent, publication, or other information cited is "prior art" or is material to patentability for this invention unless specifically designated as such. In accordance with 37 CFR 1.97(g), the filing of this Information Disclosure Statement shall not be construed to mean that a search has been made or that no other information material to patentability, as defined in 37 CFR 1.56(b), exists.

Respectfully submitted,

Date: <u>Au6. 5, 20</u>04

William D. Sabo, Esq.

Registration No. 27,465

Attorney for Applicants

IBM Corporation

Intellectual Property Law - Mail Stop 972E

1000 River Street

Essex Junction, Vermont 05452

INFORMATION DISCLOSURE CITATION (Use several sheets if necessary)				ocket Number (Optional) BUR92004008	86US1	Application Number 10/710602						
				A	Applicant(s) Rankin et al.							
				F	Filing Date Group Art Unit							
U.S. PATENT DOCUMENTS												
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	<u> </u>		OTHER DO	OCUMENTS	S (Including Aut	hor, Title, Date,	Pertinent Pages, Et	tc.)				
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		Chiong et al., CONTRADISCLOSURE Bulletin, Vo	Chiong et al., CONTRAST ENHANCEMENT OF RESIST IMAGES BY SURFACE CROSSLINKAGE, IBM Technical Disclosure Bulletin, Vol. 31, No. 3, August 1988, page 349.									
EXAMINER				1	DATE CONSIDERED							
EXAMINE not conside	ER: Initiered. In	ial if citation considered, whether iclude copy of this form with next	or not citation is in a	conformance	e with MPEP Section 60	9; Draw line thr	ough citation if no	t in conformance and				